ANOMALY DETECTION METHOD AND PLASMA PROCESSING DEVICE

ABSTRACT

An anomaly detection method includes changing at least one processing condition of plasma processing in cycles. The plasma processing is performed in a chamber in a plasma processing device. The anomaly detection method further includes obtaining, in a series of the cycles being repeated and in which the at least one processing condition is changed, a value of at least one state of plasma in the chamber at each phase in each of the cycles in the series. The anomaly detection method further includes detecting an anomaly in the plasma by comparing the value of the at least one state at each phase in each of the cycles in the series with a reference value obtained based on values of the at least one state at corresponding phases in one or more preceding cycles in the series.

Fig. 4